

Admont



This project has received funding from the ECSEL Joint Undertaking under grant agreement No 661796.

This Joint Undertaking receives support from the European Union's Horizon 2020 research and innovation programme and Germany, Finland, Sweden, Italy, Austria, Hungary."



ADMONT

ADMONT Essential Capabilities & Services FhG-FEP Dresden

Information for potential ADMONT pilot line user

Status 07/2015

Advanced Distributed Pilot Line for More-than-Moore Technologies

Who is ADMONT?

Advanced Distributed Pilot Line for More-than-Moore Technologies

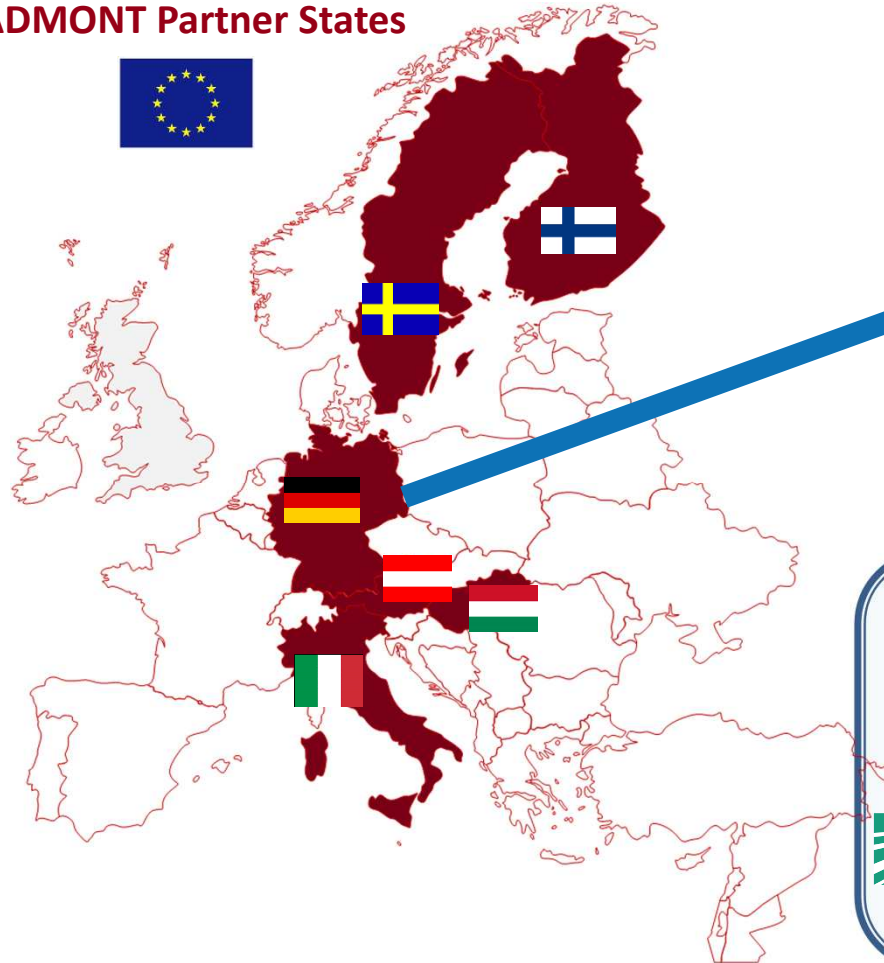
ADMONT is a **multi-KET pilot line** driven by a **combination of technology platforms** in Dresden carried by industry and research institutes serving pilot line clients in Europe


- ADMONT is organised along the **value chain** from wafer material, CMOS wafer, sensor and OLED processing to silicon system integration in one production flow
- ADMONT is an **ECS** (European Electronics Components and Systems) **ecosystem** in **Saxony** for Europe with sustainable impact on economic growth and employment in the European Union
- ADMONT addresses key applications: **smart mobility, smart energy, smart health** and **smart production** in excellent agreement with the **ECSEL Multiannual Strategic Plan**
- ADMONT addresses essential capabilities: **semiconductor process equipment and materials, design technology, smart system integration**

ADMONT as a distributed More-than-Moore pilot line is unique in Europe and worldwide.


Where is ADMONT?

ADMONT Partner States






FAB
MIXED-SIGNAL FOUNDRY EXPERTS




Fraunhofer
FEP

ADMONT Pilot Line



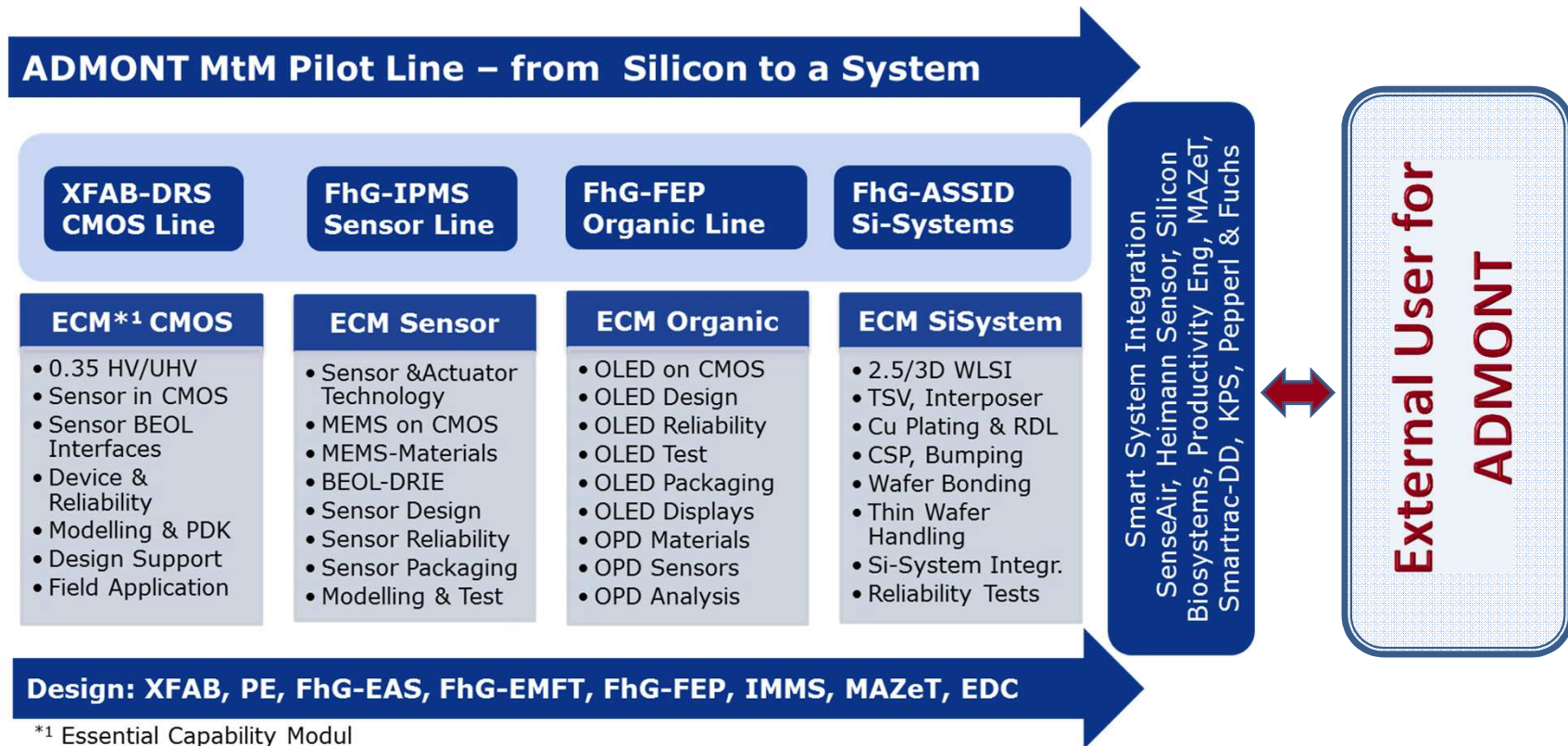
Fraunhofer
IPMS



Fraunhofer
IZM

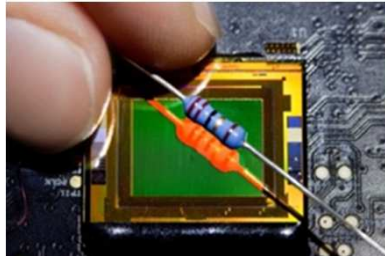
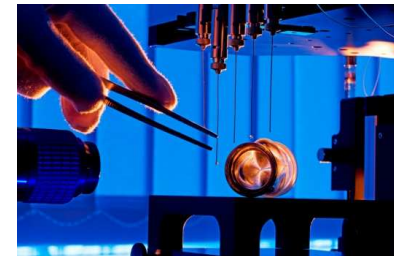
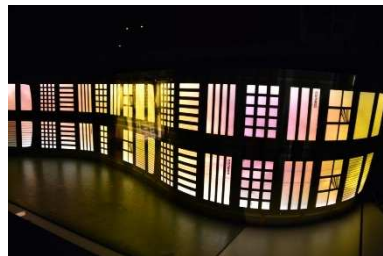
ADMONT Concept & Capabilities

- ADMONT pilot line concept, structure and excellences



- Detailed Information are available under (Link: XFAB, IPMS, FEP, ASSID)

Fraunhofer Institute for Organic Electronics, Electron Beam and Plasma Technology FEP



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Admont

 **ECSEL**
Joint Undertaking

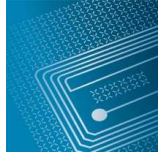
 **Fraunhofer**
FEP

Fraunhofer FEP and COMEDD

History

- 1991 foundation of the Fraunhofer FEP with approx. 70 employees of the former research institute “Manfred von Ardenne”
- 1991 – 1996 construction and extension of the Technology Center Helmsdorf
- 1998 inauguration of the Dresden part of Fraunhofer FEP at the Fraunhofer Institute Center at Winterbergstrasse
- 2002 – 2004 extension of the technology buildings at Winterbergstrasse
- 2013 inauguration of the Fraunhofer research center “resource-saving energy technologies – RESET“ by Fraunhofer FEP, Fraunhofer IKTS, and Fraunhofer IWS
- 1. July 2014 Merger of Fraunhofer COMEDD and Fraunhofer FEP

Fields of Application



**OPTICS, SENSOR TECHNOLOGY
AND ELECTRONICS**



DISPLAYS



**SMART BUILDING
AND ARCHITECTURE**



MECHANICAL ENGINEERING



ENVIRONMENT AND ENERGY



TRANSPORT



BIOMEDICAL ENGINEERING



LIGHTING



SOLAR ENERGY



PACKAGING

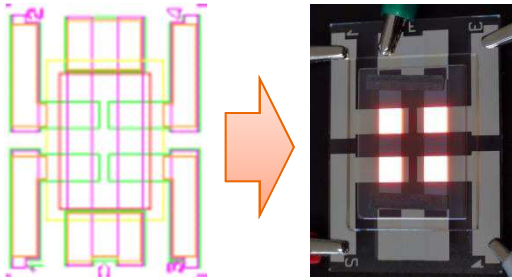


AGRICULTURE



PRESERVATION

Fraunhofer FEP services for customers



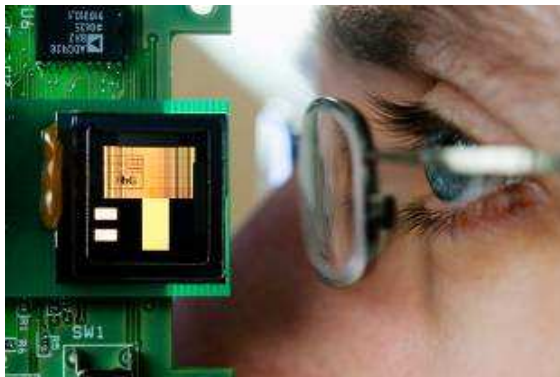
Device concept and layout



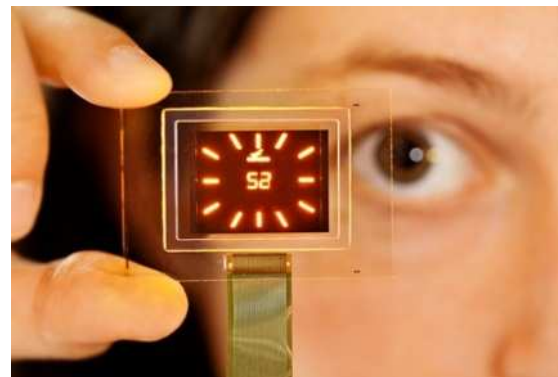
Fabrication and characterization technology



Deposition and structuring of electrodes and passivation



Integration technology for organic devices

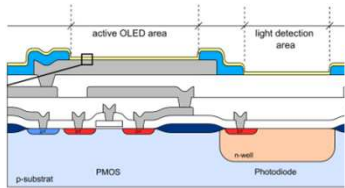


Product related R&D

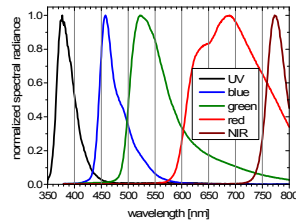


Pilot production of organic devices

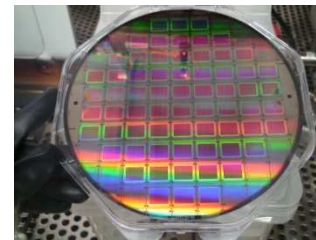
FEP offers complete chip development and demonstrator manufacturing



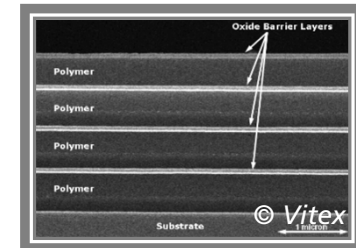
IC-Design of CMOS and transfer to wafer fab



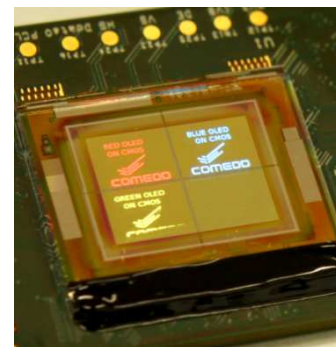
OLED and OPD development to customers needs



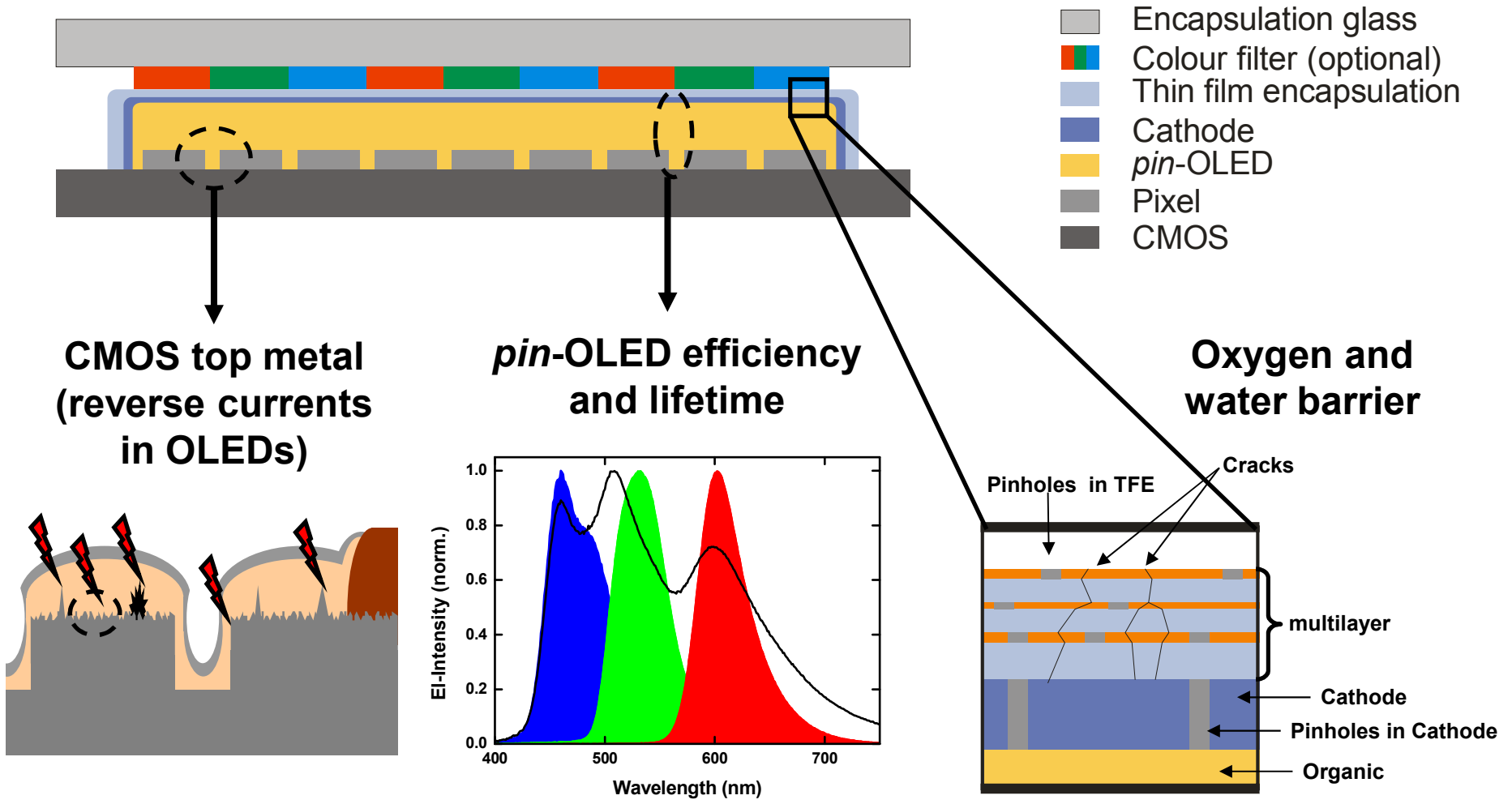
Development of sensor on 8" wafer production equipment with state of the art Vitex encapsulation



*- Software and interface development
- Wafer dicing / chip on PCB*



MAIN RESEARCH TOPICS FOR OLED MICRODISPLAYS AND SENSORS



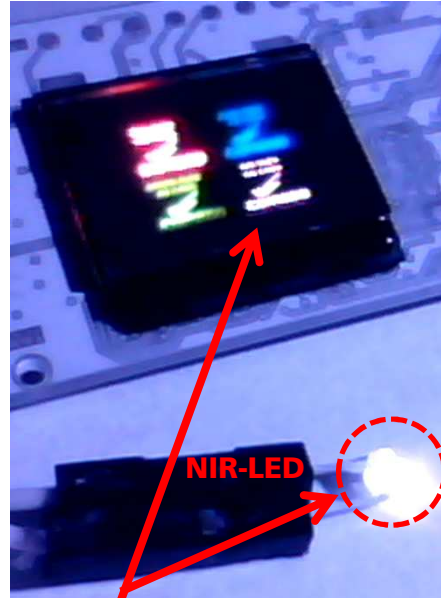
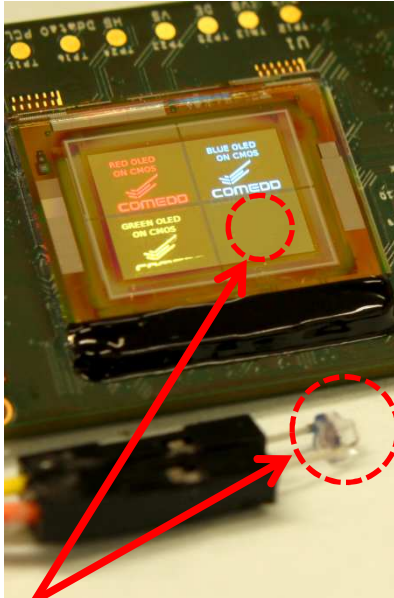
OLED/PLED Microdisplay clean room at FEP



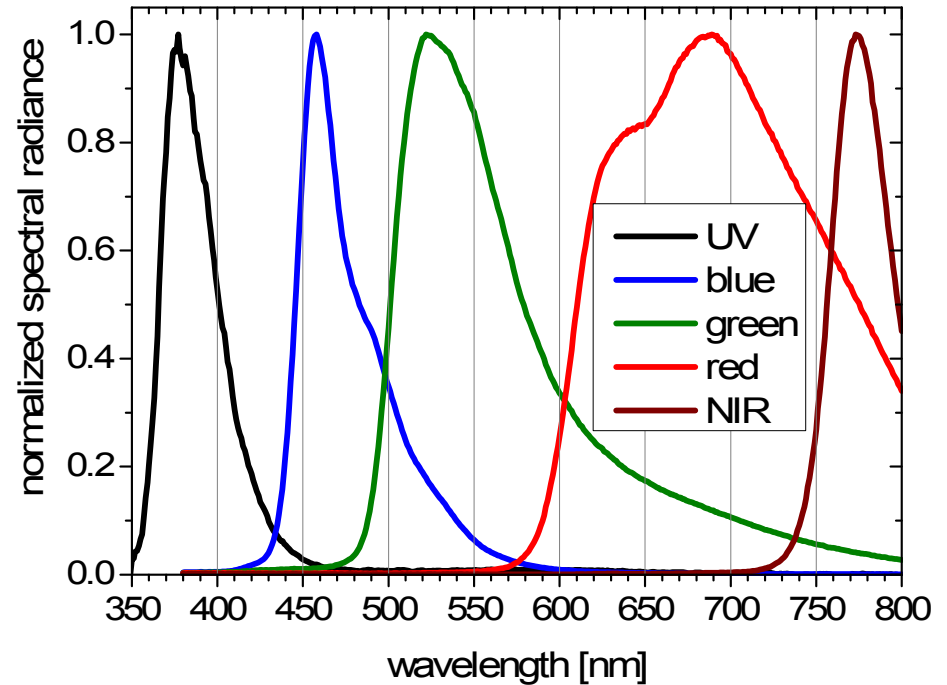
- Process flow - process line for PLED and OLED microdisplay production within 300m² class 100 clean room
 - Anode metal deposition
 - Spin coating of organics
 - Structuring of organics via etching or shadow masks
 - Cathode deposition
 - thin film encapsulation
 - 200mm wafer level device test
 - Silicon wafer to color filter lamination



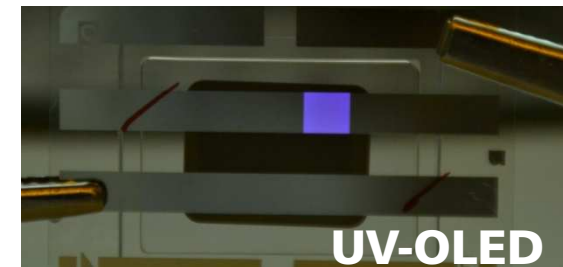
UV-VIS-NIR-OLEDs on CMOS backplanes



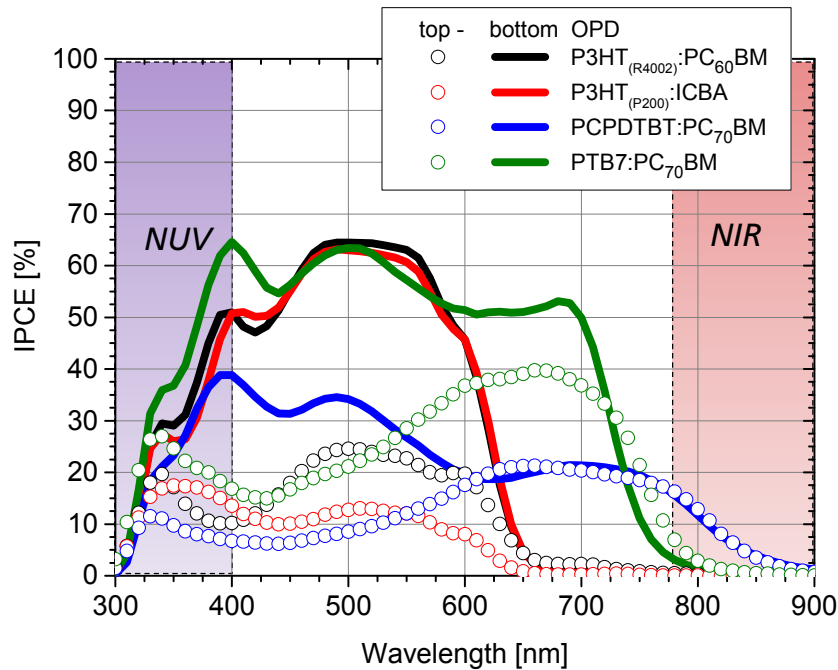
NIR-not visible for standard cameras Only visible without NIR-filter cameras



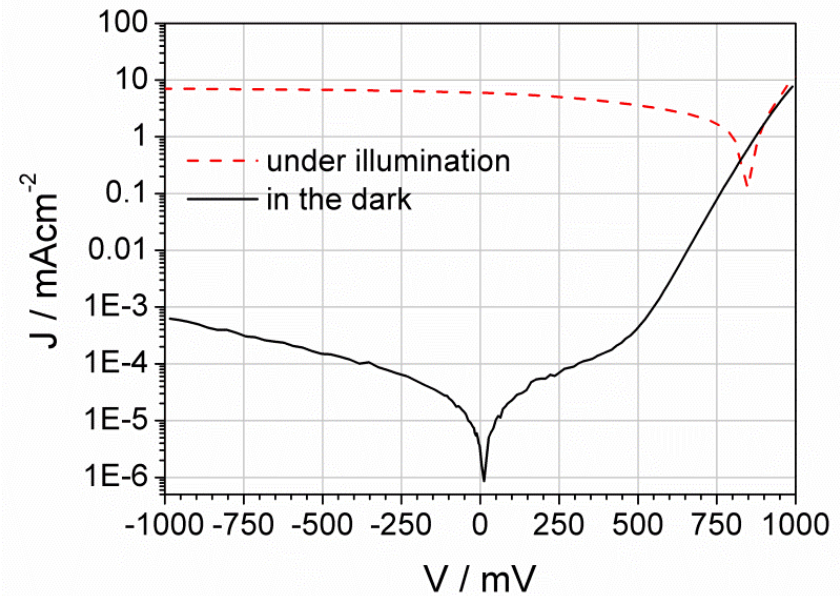
- Integration of various emission spectra within the visible range as well as in NIR and UV on CMOS.
- Peak wavelength and efficiency of all emitter can be optimized by using OLED stacks for every emitter.



Organic Photodiodes



Spectral sensitivity in dependence on the material composition.



J-V curve of an organic photodiode

- *Properties such as spectral sensitivity, capacitance and dark current can be adjusted*
- *OPDs show better sensitivity values in blue and UV than Si based photodiodes*

Contact



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*We look forward working with you from the concept phase
right through to industrial implementation.*

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